

Notice of References Cited	Application/Control No. 10/766,646	Applicant(s)/Patent Under Reexamination LEE, HEON	
	Examiner Eric B. Chen	Art Unit 1765	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,136,243	10-2000	Mehregany et al.	264/162
	B	US-6,309,580	10-2001	Chou, Stephen Y.	264/338
	C	US-2002/0137331	09-2002	Chang, Ching-Yu	438/637
	D	US-6,943,117	09-2005	Jeong et al.	438/694
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, Silicon Processing for the VLSI Era, 2002, Lattice Press, Vol. 4, p. 313.
	V	Rossnagel et al., Handbook of Plasma Processing, 1990, Noyes Publications, pp. 198-199.
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
 Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.